GenISys
Booth # 19

Software solutions for optimizing micro & nano fabrication processes

MASKER | BEAMER | LAB | TRACER | ProSEM | VIEWER

I N V I T A T I O N   *Tuesday, 28th May 2019*

EIPBN Minneapolis 2019

Location : Hyatt Regency
1300 Nicollet Mall
Minneapolis, MN USA
Room   : Nicollet Ballroom A
Time   : 9:00 am to 3:00 pm

BEAMeeting -   Technical Workshop & Discussion   from 9:00 am till 3:00 pm

BEAMeetings are a technical exchange platform for the direct write community focused on e-beam and laser lithography, data-preparation, PEC, process correction, lithography simulation and metrology. As always we like to setup the agenda with your input! We encourage user presentations, and welcome any discussions on applications, specific issue solutions, and feature needs or requirements. **The final agenda for the meeting will be based on all of your inputs.**

The meeting is free of charge. Lunch and coffee/drinks are included. For registration just send a short e-mail to Roger McCay (mccay@genisys-gmbh.com).

If you have any colleagues who may be interested in participating this workshop, we would greatly appreciate your forwarding this information onto them.

We are looking forward to presenting you with interesting and valuable information on BEAMER.

Please visit our booth # 19 on the exhibition floor from Tues-Thurs.

Thank you,

The GenISys TEAM

GenISys
Nicollet Ballroom
A-1, 2, 3
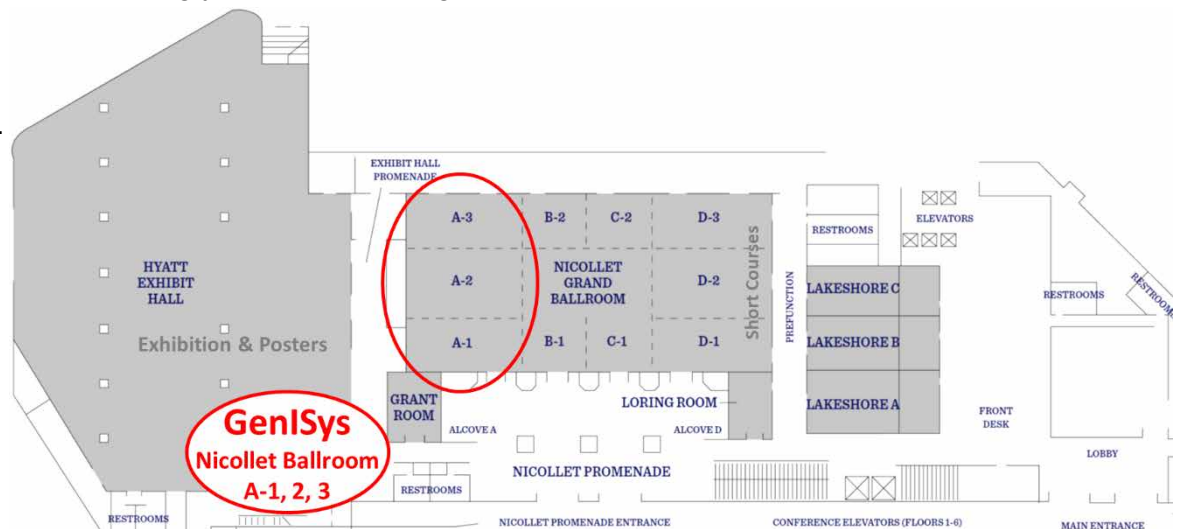
SEE AGENDA ON BACK OF THIS PAGE

BEAMeeting E-Beam & Laser Workshop
Technical Workshop & Discussion

Date: Tuesday, May 28th, 2019 - Time: 09:00 – 3:00 pm
Hyatt Regency – Room Nicolet A1

Agenda

Ulrich Hofmann GenISys	Welcome & Introduction GenISys Update	9:00 am
Doc Daugherty GenISys	GenISys at EIPBN	9:30
Rick Bojko GenISys	Making the Rules: Laser & Ebeam Use Cases for Rule OPC	9:40
MIT Marco Colangelo	Process Analysis using ProSEM	10:00
	Coffee Break	10:25
Kashif Masud Awan UBC	Improvement of Exposure Latitude in an E-beam Lithography Process	10:45
Doc Daugherty GenISys	Simplifying Complex Flows with Variables and Quick-Access	11:10
Amrita Banerjee Cornell	Staying Sharp - Improving Corners at the Nanoscale	11:35
	Lunch	12:00 pm
Doc Daugherty GenISys	Putting Fields in their Place	12:45
Kerim Arat TU Delft - NL	Monte-Carlo Simulation of Charge-Induced Pattern Displacement in E-Beam Lithography	1:10
Gerald Lopez Univ. Of Penn.	DisCharge: A Perspective on Charge Dissipation Layer Testing for Non-Conductive Subtrates	1:35
	Coffee Break	2:00
Thomas Michels GenISys	What's New in BEAMER and Roadmap Discussion	2:20
	FINAL Closing	3:00

Agenda is subject to change

GenISys
Advancing the Standard